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11-20-03

PATENT  
Customer No. 22,852  
Attorney Docket No. 04329.2409

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Kei YOSHIKAWA et al.

Application No.: 09/662,219

Filed: September 14, 2000

For: PATTERN CORRECTING  
METHOD OF MASK FOR  
MANUFACTURING A  
SEMICONDUCTOR DEVICE AND  
RECORDING MEDIUM HAVING  
RECORDED ITS PATTERN  
CORRECTING METHOD

Group Art Unit: 2623

Examiner: S. Ahmed

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Technology Center 2600

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**AMENDMENT**

In response to the Office Action dated July 14, 2003, the period for response having been extended to November 14, 2003, by a request for extension of one month and fee payment filed concurrently herewith, please reexamine and reconsider the application in view of the amendments and appended remarks.

**Amendments to the Specification** are included in this paper.

**Amendments to the Claims** are reflected in the listing of claims in this paper.

**Remarks/Arguments** follow the amendment sections of this paper.

**Attachments** to this amendment include a new Abstract.

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